

Title (en)

METHOD FOR MASKING A SURFACE COMPRISING SILICON OXIDE

Title (de)

VERFAHREN ZUM MASKIEREN EINER SILIZIUMOXID HALTIGEN OBERFLÄCHE

Title (fr)

PROCÉDÉ POUR MASQUER UNE SURFACE CONTENANT DE L'OXYDE DE SILICIUM

Publication

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Application

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Abstract (en)

[origin: WO2014166706A1] The invention relates to a method for masking a surface, in particular a surface having silicon oxide, aluminum or silicon, having the method steps: a) providing a substrate having a surface to be masked, in particular having a surface having silicon oxide, aluminum or silicon; and b) producing a defined masking pattern by locally selective forming of colloidal silicon oxide on the surface. The method according to the invention allows for the creating of an extremely stable masking in a simple and cost-effective manner, in contrast to a plurality of etching media, in particular in contrast to hydrofluoric acid, in order to thus create extremely accurate and defined structures such as by an etching process. The invention further relates to an electronic component and to the use of colloidal silicon oxide for locally selective masking of a surface to be treated.

IPC 8 full level

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Citation (search report)

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